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positioned substantially coaxial with a center of said susceptor, and at least three arms radially extending from an upper end of said main shaft, each said arm having a distal end provided with a protrusion directed toward said susceptor; wherein a peripheral portion of a lower surface of said susceptor being formed with depressions, each said depression having an inside diameter substantially identical to an outside diameter of said protrusion, adapted to engage said protrusion, wherein each of said depressions extend in a radial direction of said susceptor, and wherein a portion of each of said depressions extends along a direction substantially parallel to a plane defined by at least one of a top surface of said susceptor or a bottom surface of said susceptor so as to permit movement of said susceptor in a substantially radial direction relative to said protrusions along said depressions.

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3. A semiconductor production apparatus according to claim 1, wherein said depressions have an elongated form extending in a radial direction of said susceptor.

C3
14. A semiconductor production apparatus comprising:
a processing chamber;
a susceptor disposed within said process chamber and having an upper surface for mounting a semiconductor wafer thereon;
a support shaft disposed within said process chamber for supporting said susceptor; and
a heating source disposed so as to heat the wafer mounted on said susceptor,